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 (12) (B1)

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	(24)	2002 10 14

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(21)	10 - 2000 - 0070712	(65)	2002 - 0040998
(22)	2000 11 25	(43)	2002 05 31

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(73) 1355 - 26

1 951 - 20 26/3 3 - 101

(72) 219 - 27

1 951 - 20 26/3 3 - 101

(74)

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(54)

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(Full Color)										EL			
1	(3),	2	,	(4),	3	(1)	(5)	(2)		;	1	(3)	(2)
	,	2		(4)						;	3	(5)	
2	(4)	(6a)			(6)			(6a)		2	(4)	(6a)	(7a)
			;			(7a)		(8a)		;		(8a)	(9)
	;	3			(5)				(7b),			(8b)	(9)

1 EL  
2 10  
<  
1 : 2 : (ITO ) ,  
3 : 1 , 4 : 2 ,  
5 : 3 , 7 : ,  
8 : 9 :  
22 : (Red) , 23 :  
24 : (Blue) .

(Electro - Luminescence, "EL" )  
(Full Color)

EL

EL

EL PDA , ,  
가 .

1 (Passive Matrix) 가 EL  
 EL , 1 , , (10)  
 ITO(Indium Tin Oxide) ( ) (20) / /  
 (30) . (20) (30) ( ) (40)  
 . EL SUS ( )  
 . 가 가

EL (40) " - " (30) 가 , ITO (20) . , ITO (20) (40) " +" (20) 가  
가 , (10) .

## EL (Organic Material)

R.G.B.

가

가

가

1

가

가

1 (3), 2 (4), 3 (5) (1) (2) ; 1 (3)  
     , 2 (4) (6a) (4) (6) (6a); 3 (5) (7a) (8a); 2 (4) (6a) (7b), (8a) (9)  
 2 (4) ; ; (5) ; ; (8b) (9)  
 a) ; 3 (5)

1 (3), 2 (4) 3 (5) SiO<sub>2</sub>, SiNx

3 (5) 1 (3) 2 (4)

CMP(Chemical Mechanical Polishing)  
가

(Dry Etching)

(22) , (23) (22);  
 (23) (24) ;

(2) , , (1); (1) (2);  
     , 1 (3); 1 (3)  
 6a) (6a) 2 (4); 2 (4) , 2 (4) ( (6) 3 (5); 1 (3) 2 (4) (7a); (7a)  
 6a) , 2 (4) (8a); (8a) , 3 (5)  
 (9);

, , (22); (23); (22);  
 (23) (24);

2 10  
2 10

2

(1)

3

(1)

ITO

) (2)

4

(2)

1

(3)

(4)

3

(5)

$$, \quad 5 \quad , \quad 1 \quad (3) \quad . \quad , \quad 2 \quad (4)$$

$$(6a) \quad . \quad . \quad . \quad 3 \quad (5) \quad (6a) \quad (6)$$

6 , , (Blue) (7a) . , (7a) 1 (3)  
 (6a) . , (7a) 2 (4)  
 2 (4) 3 (5) . 3 (5)  
 (7b) .

$$7 \quad , \quad (7a) \quad (7b) \quad (8a, 8b)$$

(7b) \quad (8b) \quad . \quad (8a, 8b)

, 8 , (8a, 8b) (9) . , (9)  
 3 (5) (6) .  
 가 .

, 9 , (9) 3 (5)  
CMP(Chemical Mechanical Polishing) (Dry Etching)  
가 , 가 ( , ) .

,

EL  
가 , 가

, (Anode) (Cathode) 가 ,

가

가

(57)

1.

(1) (2) ;

(2) 1 (3), 2 (4), 3 (5) ;

1 (3)  
3 (5) 2 (4) (6a) (6) ;

2 (4) (6a) (7a) ;

(7a) (8a) ;

(8a) (9) ;

3 (5) (7b), (8b) (9) ;

2.

1 , 1 (3), 2 (4) 3 (5) SiO<sub>2</sub>, SiNx

3.

1 , 3 (5) 1 (3) 2 (4)

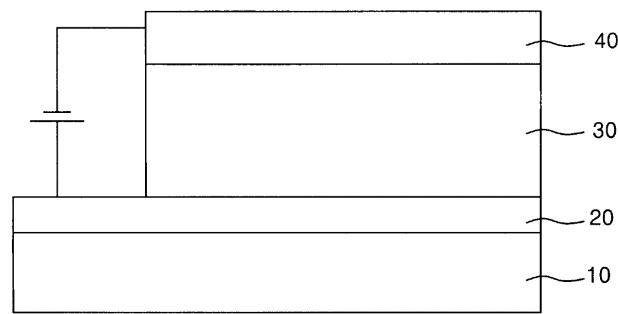
4.

1 , CMP(Chemical Mechanical Polishing)

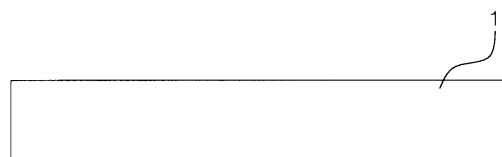
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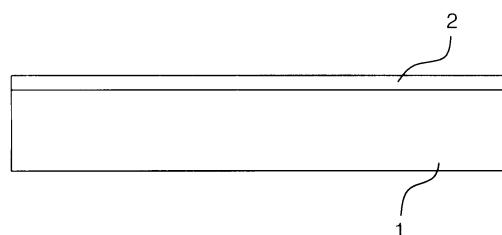
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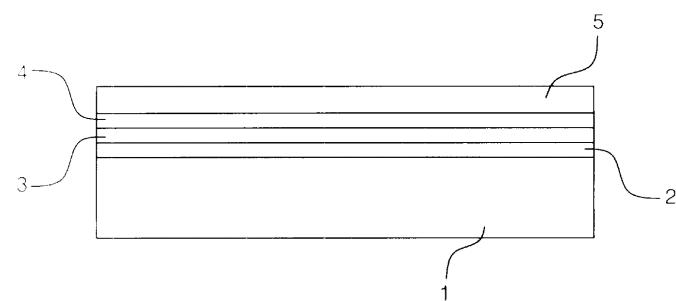
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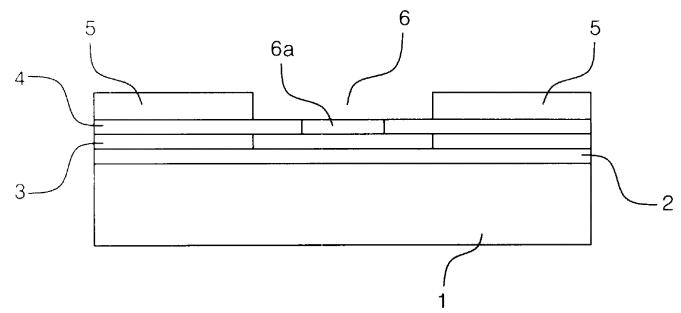
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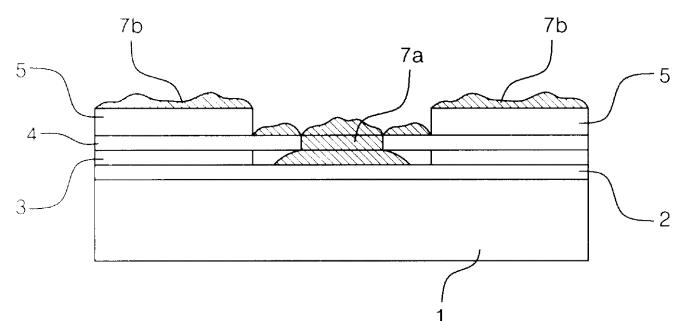
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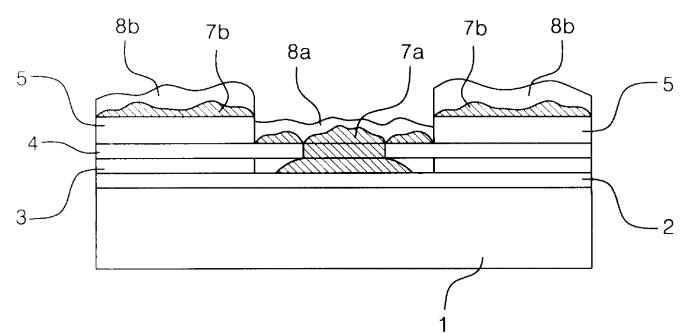
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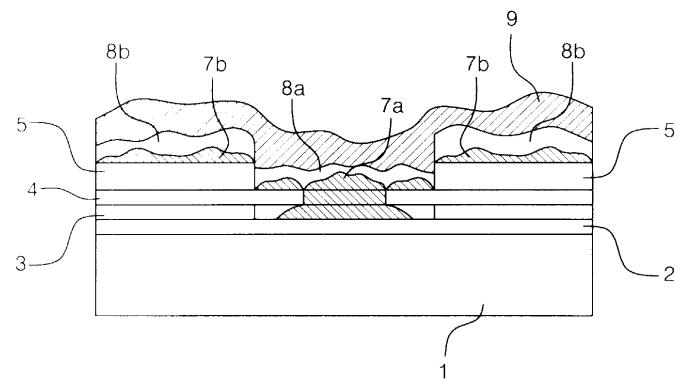
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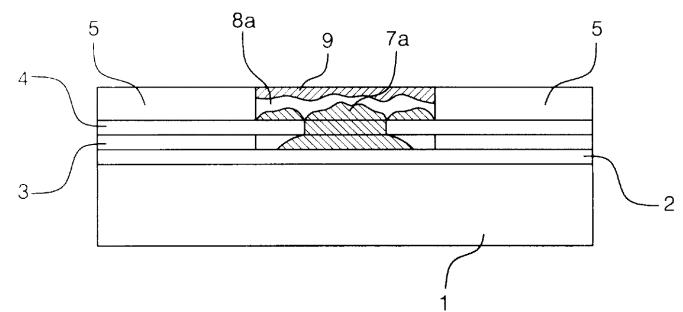
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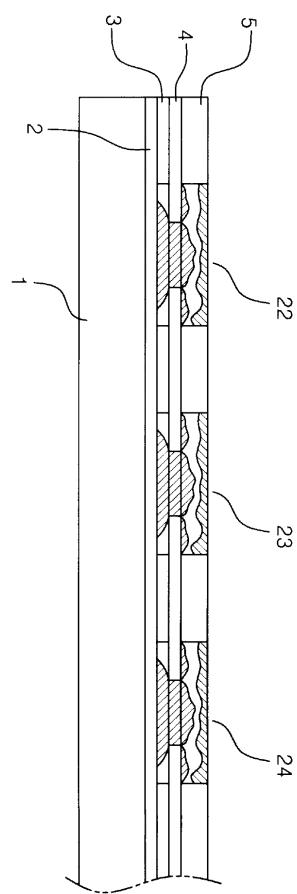
8



9



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专利名称(译)	有机电致发光显示面板及其制造方法		
公开(公告)号	KR100358503B1	公开(公告)日	2002-10-30
申请号	KR1020000070712	申请日	2000-11-25
[标]申请(专利权)人(译)	ELIATECH 公园胜利 Bakwonseok		
申请(专利权)人(译)	电梯技术有限公司. Bakwonseok		
当前申请(专利权)人(译)	电梯技术有限公司. Bakwonseok		
[标]发明人	KANG SINKYU 강신규 PARK WON SEOCK 박원석		
发明人	강신규 박원석		
IPC分类号	H05B33/10		
代理人(译)	孙某EUN JIN		
其他公开文献	KR1020020040998A		

**摘要(译)**

本发明涉及一种用于提高全色精细图案的对准精度的有机EL显示板及其制造方法。为此目的，提供一种制造薄膜晶体管的方法，包括：在透明基板(1)上沿一个方向沉积阳极层(2)；在阳极层(2)的上表面上依次形成第一绝缘层(3)，第二绝缘层(4)和第三绝缘层(5)；第一在第二绝缘层(4)中形成宽度窄于凹槽的凹槽6a，并且在绝缘层3中形成宽度小于凹槽宽度的凹槽6a，形成宽度大于绝缘层(4)的凹槽(6a)的凹槽(6)；在第二绝缘层(4)的槽(6a)内形成发光层(7a)；阴极层8a形成在发光层7a的上表面上步骤；在阴极层(8a)的上表面上形成保护层(9)；去除位于第三绝缘层(5)的上表面上的发光材料残留物(7b)，阴极材料残留物(8b)和保护层(9)以平坦化有机发光显示面板提供了一种方法及其面板。9 指数方面 - 1 - 有机，电致发光，面板，沉积，绝缘体，金属

